

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/659,119	09/10/2003	Mitsuo Kawasaki	9281-4620	3593
DDINIVE UODI	7590 02/21/2007 ER GILSON & LIONE	EXAMINER		
P.O. BOX 1039	95		BERNATZ, KEVIN M	
CHICAGO, IL 60610			ART UNIT	PAPER NUMBER
			1773	
SHORTENED STATUTOR	RY PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE	
3 MO	ONTHS	02/21/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

		Application No.	Applicant(s)	
,		10/659,119	KAWASAKI ET AL.	
	Office Action Summary	Examiner	Art Unit	
		Kevin M. Bernatz	1773	
	The MAILING DATE of this communication ap		e correspondence address	
Period fo	, ,			
WHIC - Exte after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPL CHEVER IS LONGER, FROM THE MAILING D nsions of time may be available under the provisions of 37 CFR 1. SIX (6) MONTHS from the mailing date of this communication. O period for reply is specified above, the maximum statutory period re to reply within the set or extended period for reply will, by statut reply received by the Office later than three months after the mailir ed patent term adjustment. See 37 CFR 1.704(b).	OATE OF THIS COMMUNICATION 136(a). In no event, however, may a reply be will apply and will expire SIX (6) MONTHS from the course the application to become ABANDO	ON. timely filed om the mailing date of this communication NED (35 U.S.C. § 133).	
Status				
1)	Responsive to communication(s) filed on		•	
·		—· s action is non-final.		
=	Since this application is in condition for allower	•	prosecution as to the merits is	;
,—	closed in accordance with the practice under	,		
Dispositi	ion of Claims			
·	Claim(s) <u>1,3-5,7,8,12-16 and 20-25</u> is/are pen	ding in the application		
	4a) Of the above claim(s) is/are withdra			
	Claim(s) is/are allowed.			
·	Claim(s) <u>1,3-5,7,8,12-16 and 20-25</u> is/are reje	ected.		
7)	Claim(s) is/are objected to.			
8)[Claim(s) are subject to restriction and/o	or election requirement.		
Applicati	on Papers			
9)□	The specification is objected to by the Examine	er.		
=	The drawing(s) filed on is/are: a) ☐ acc		e Examiner.	
•—	Applicant may not request that any objection to the	•		
	Replacement drawing sheet(s) including the correct		···	I).
11)	The oath or declaration is objected to by the E	xaminer. Note the attached Office	ce Action or form PTO-152.	
Priority u	ınder 35 U.S.C. § 119			
12)	Acknowledgment is made of a claim for foreigr	n priority under 35 U.S.C. § 119	(a)-(d) or (f).	
a)[☐ All b)☐ Some * c)☐ None of:			
	1. Certified copies of the priority documen	ts have been received.	,	
	2. Certified copies of the priority document	ts have been received <u>i</u> n Applica	ation No	
	3. Copies of the certified copies of the price	rity documents have been recei	ved in this National Stage	
	application from the International Burea	• • • •		
* S	See the attached detailed Office action for a list	of the certified copies not recei	ved.	
Attachmen	t(s)	•		
	e of References Cited (PTO-892)	4) Interview Summa		
	e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO/SB/08)	Paper No(s)/Mail 5) Notice of Informa		
	r No(s)/Mail Date <u>12/08/06</u> .	6) Other:		

Art Unit: 1773

DETAILED ACTION

Response to Amendment

- 1. Amendments to claims 1 and 8 and cancellation of claims 6, 9 and 19, filed on December 8, 2006, have been entered in the above-identified application.
- 2. The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.

Examiner's Comments

3. Regarding the limitation(s) "epitaxially disposed in the stack" in the claims, the Examiner has given the term(s) the broadest reasonable interpretation(s) consistent with the written description in Applicants' specification as it would be interpreted by one of ordinary skill in the art. *In re Morris*, 127 F.3d 1048, 1054-55, 44 USPQ2d 1023, 1027 (Fed. Cir. 1997); *In re Donaldson Co., Inc.*, 16 F.3d 1190, 1192-95, 29 USPQ2d 1845, 1848-50 (Fed. Cir. 1994). See MPEP 2111. Specifically, the Examiner notes that the broadest reasonable interpretation of the term "epitaxially disposed" is simply that the crystals are deposited on each other and correlated in some manner. The Examiner notes that the exact correlation (e.g. an upper crystal corresponds to only a single lower crystal, the upper crystal is larger than the lower crystal, the upper crystal is smaller than the lower crystal, etc) is not claimed, and as such the claim limitation is essentially open to any correlation. I.e. for the purposes of evaluating the prior art "epitaxially disposed" has been interpreted to simply require two crystalline materials that are

Art Unit: 1773

disposed on top of each other in close proximity thereto. The Examiner has *not* taken the term "epitaxially disposed" to mean "directly adjacent" and should Applicants desire to require that all the fine crystals are directly adjacent to each other, they should clearly amend the claims to positively recite this feature.

Request for Continued Examination

4. A Request for Continued Examination (RCE) under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on December 8, 2006 has been entered. An action on the RCE follows.

Claim Rejections - 35 USC § 103

5. Claims 1, 3 – 5, 21, 22 and 25 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hiramoto et al. (U.S. Patent No. 5,849,400) in view of Yoshikawa et al. (U.S. Patent No. 6,132,892).

Regarding claim 1, Hiramoto et al. disclose a plated magnetic film comprising Co and Fe, wherein the plated magnetic film comprises columnar crystals extending in a film thickness direction, wherein a stack of fine crystals having an average crystal particle diameter of 200 Å or less constitutes the columnar crystals, the fine crystals being epitaxially disposed in the stack, and wherein a plurality of the columnar crystals

Art Unit: 1773

are provided adjacent one another in a film surface direction with grain boundaries extending in the film thickness direction and separating the columnar crystals (see Paragraph No. 8 of the Office Action mailed February 9, 2006 and Paragraph No. 8 of the Office Action mailed August 8, 2006, as well as Paragraph 3 above).

Hiramoto et al. fail to disclose the fine crystals having a body centered cubic structure, nor the (110) plane meeting Applicants' claimed limitations.

However, Yoshikawa et al. teach that it is known in the art to form soft magnetic films comprising Co and Fe in the form of fine crystals (*Figures and Abstract*) wherein the crystals and (110) plane are preferentially controlled to meet Applicants' claimed limitations inorder to provide a large magnetic flux density and large saturation magnetization (*col.* 6, lines 10 – 30; and col. 11, line 35 bridging col. 12, line 59).

It would therefore have been obvious to one of ordinary skill in the art at the time of the applicant(s) invention to modify the device of Hiramoto et al. to utilize a FeCo alloy meeting Applicants' claimed bcc and (110) plane limitations as taught by Yoshikawa et al., since such a structure provides a large magnetic flux density and large saturation magnetization.

Regarding claims 3 – 5 and 22, Yoshikawa et al. disclose CoFe films meeting applicants' claimed composition and property limitations (*Table 5*).

Regarding claims 21 and 25, Hiramoto et al. disclose the claimed limitations as relied upon in Paragraph No. 8 of the Office Action mailed February 9, 2006 and Paragraph No. 8 of the Office Action mailed August 8, 2006.

Art Unit: 1773

6. Claim 23 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hiramoto et al. in view of Yoshikawa et al. as applied above, and further in view of Osaka et al. (U.S. Patent No. 6,063,512).

Hiramoto et al. and Yoshikawa et al. are relied upon as described above.

Neither of the above disclose a magnetic CoFe film meeting applicants' claimed stress limitation.

However, Osaka et al. teach the importance of minimizing the film stress of a soft magnetic alloy for use in a magnetic head inorder to insure a film of uniform quality (*col.* 5, lines 55 – 62 and col. 7, lines 39 - 45. The Examiner deems that it would have been obvious to one having ordinary skill in the art to have determined the optimum value of a results effective variable such as the magnitude of the film stress through routine experimentation, especially given the teaching in Osaka et al. regarding the desire to minimize the film stress to insure a film of uniform quality. *In re Boesch*, 205 USPQ 215 (CCPA 1980); *In re Geisler*, 116 F. 3d 1465, 43 USPQ2d 1362, 1365 (Fed. Cir. 1997); *In re Aller*, 220 F.2d, 454, 456, 105 USPQ 233, 235 (CCPA 1955).

7. Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hiramoto et al. in view of Yoshikawa et al. as applied above, and further in view of Sato et al. (U.S. Patent App. No. 2003/0151851 A1).

Hiramoto et al. and Yoshikawa et al. are relied upon as described above.

Neither of the above disclose a surface roughness meeting applicants' claimed limitations.

Art Unit: 1773

However, Sato et al. teach that it is known to form pole pieces of FeCo material to possess surface roughness values meeting applicants' claimed limitations inorder to insure that the surface is sufficiently flat for use as a pole piece in a thin-film magnetic head (*Paragraphs 0102 and 0145*).

It would therefore have been obvious to one of ordinary skill in the art at the time of the applicant(s) invention to modify the device of Hiramoto et al. in view of Yoshikawa et al. to use a FeCo layer meeting applicants' claimed surface roughness limitations as taught by Sato et al. since such a surface roughness is necessary to insure that the surface is sufficiently flat for use as a pole piece in a thin-film magnetic head.

8. Claim 24 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hiramoto et al. in view of Yoshikawa et al. as applied above, and further in view of Komuro et al. (U.S. Patent No. 6,034,847).

Hiramoto et al. and Yoshikawa et al. are relied upon as described above.

Neither of the above disclose a specific resistance meeting applicants' claimed limitations.

However, Komuro et al. teach the importance of controlling the resistivity (i.e. the specific resistance) of a soft magnetic film for use in a magnetic head application to within applicants' claimed range inorder to insure improved radio frequency performance (abstract; col. 2, lines 32 – 37; and col. 3, line 46 bridging col. 4, line 2).

The Examiner deems that it would have been obvious to one having ordinary skill in the art to have determined the optimum value of a results effective variable such as

Art Unit: 1773

the specific resistance/resistivity through routine experimentation, especially given the teaching in Komuro et al. regarding the desire to possess resistance values meeting applicants' claimed limitations inorder to insure improved radio frequency performance.

9. Claims 1, 3 – 5, 21, 22 and 25 are rejected under 35 U.S.C. 103(a) as being unpatentable over Funayama et al. (U.S. Patent App. No. 2003/0197982 A1) in view of Yoshikawa et al. ('892).

Regarding claim 1, Funayama et al. disclose a plated magnetic film comprising

Co and Fe, wherein the plated magnetic film comprises columnar crystals extending in a
film thickness direction, wherein a stack of fine crystals having an average crystal
particle diameter of 200 Å or less constitutes the columnar crystals, the fine crystals
being epitaxially disposed in the stack, and wherein a plurality of the columnar crystals
are provided adjacent one another in a film surface direction with grain boundaries
extending in the film thickness direction and separating the columnar crystals (see

Paragraph No. 9 of the Office Action mailed February 9, 2006 and Paragraph No. 9 of
the Office Action mailed August 8, 2006, as well as Paragraph 3 above).

Funayama et al. fail to disclose the fine crystals having a body centered cubic structure, nor the (110) plane meeting Applicants' claimed limitations.

However, Yoshikawa et al. teach that it is known in the art to form soft magnetic films comprising Co and Fe in the form of fine crystals (*Figures and Abstract*) wherein the crystals and (110) plane are preferentially controlled to meet Applicants' claimed

Art Unit: 1773

limitations inorder to provide a large magnetic flux density and large saturation magnetization (col. 6, lines 10 – 30; and col. 11, line 35 bridging col. 12, line 59).

It would therefore have been obvious to one of ordinary skill in the art at the time of the applicant(s) invention to modify the device of Funayama et al. to utilize a FeCo alloy meeting Applicants' claimed bcc and (110) plane limitations as taught by Yoshikawa et al., since such a structure provides a large magnetic flux density and large saturation magnetization.

Regarding claims 3 – 5, 21 and 22, Yoshikawa et al. disclose CoFe films meeting applicants' claimed composition and property limitations (*Table 5*).

Regarding claim 25, Funayama et al. disclose the claimed limitations as relied upon in Paragraph No. 9 of the Office Action mailed February 9, 2006 and Paragraph No. 9 of the Office Action mailed August 8, 2006.

10. Claim 23 is rejected under 35 U.S.C. 103(a) as being unpatentable over Funayama et al. in view of Yoshikawa et al. as applied above, and further in view of Osaka et al. ('512).

Funayama et al. and Yoshikawa et al. are relied upon as described above.

Neither of the above disclose a magnetic CoFe film meeting applicants' claimed stress limitation.

However, Osaka et al. teach the importance of minimizing the film stress of a soft magnetic alloy for use in a magnetic head inorder to insure a film of uniform quality (*col.* 5, lines 55 – 62 and col. 7, lines 39 - 45. The Examiner deems that it would have been

Art Unit: 1773

obvious to one having ordinary skill in the art to have determined the optimum value of a results effective variable such as the magnitude of the film stress through routine experimentation, especially given the teaching in Osaka et al. regarding the desire to minimize the film stress to insure a film of uniform quality. *In re Boesch*, 205 USPQ 215 (CCPA 1980); *In re Geisler*, 116 F. 3d 1465, 43 USPQ2d 1362, 1365 (Fed. Cir. 1997); *In re Aller*, 220 F.2d, 454, 456, 105 USPQ 233, 235 (CCPA 1955).

11. Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over Funayama et al. in view of Yoshikawa et al. as applied above, and further in view of Sato et al. ('851 A1).

Funayama et al. and Yoshikawa et al. are relied upon as described above.

Neither of the above disclose a surface roughness meeting applicants' claimed limitations.

However, Sato et al. teach that it is known to form pole pieces of FeCo material to possess surface roughness values meeting applicants' claimed limitations inorder to insure that the surface is sufficiently flat for use as a pole piece in a thin-film magnetic head (*Paragraphs 0102 and 0145*).

It would therefore have been obvious to one of ordinary skill in the art at the time of the applicant(s) invention to modify the device of Funayama et al. in view of Yoshikawa et al. to use a FeCo layer meeting applicants' claimed surface roughness limitations as taught by Sato et al. since such a surface roughness is necessary to

Art Unit: 1773

insure that the surface is sufficiently flat for use as a pole piece in a thin-film magnetic head.

12. Claim 24 is rejected under 35 U.S.C. 103(a) as being unpatentable over Funayama et al. in view of Yoshikawa et al. as applied above, and further in view of Komuro et al. ('847).

Funayama et al. and Yoshikawa et al. are relied upon as described above.

Neither of the above disclose a specific resistance meeting applicants' claimed limitations.

However, Komuro et al. teach the importance of controlling the resistivity (i.e. the specific resistance) of a soft magnetic film for use in a magnetic head application to within applicants' claimed range inorder to insure improved radio frequency performance (abstract; col. 2, lines 32 – 37; and col. 3, line 46 bridging col. 4, line 2).

The Examiner deems that it would have been obvious to one having ordinary skill in the art to have determined the optimum value of a results effective variable such as the specific resistance/resistivity through routine experimentation, especially given the teaching in Komuro et al. regarding the desire to possess resistance values meeting applicants' claimed limitations inorder to insure improved radio frequency performance.

Art Unit: 1773

13. Claims 8, 9, 12 – 16 and 19 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yoshikawa et al. ('892) in view of Hitachi, LTD (JP 62-226413 A), Hiramoto et al. ('400) and Sato et al. ('851 A1) for the reasons of record as set forth in Paragraph 14 of the Office Action mailed August 8, 2006 and in Paragraph 14 of the Office Action mailed February 9, 2006.

Regarding the amended limitations regarding the bcc crystal structure and the (110) plane, the Examiner notes that Yoshikawa et al. teach that it is known in the art to form soft magnetic films comprising Co and Fe in the form of fine crystals (*Figures and Abstract*) wherein the crystals and (110) plane are preferentially controlled to meet Applicants' claimed limitations inorder to provide a large magnetic flux density and large saturation magnetization (*col. 6, lines 10 – 30; and col. 11, line 35 bridging col. 12, line 59*).

14. Claim 20 is rejected under 35 U.S.C. 103(a) as being unpatentable over Yoshikawa et al. ('892) in view of Hitachi, LTD (JP 62-226413 A), Hiramoto et al. ('400) and Sato et al. ('851 A1) as applied above, and further in view of Moran (U.S. Patent No. 6,574,854 B1) for the reasons of record as set forth in Paragraph No. 15 of the Office Action mailed August 8, 2006 and in Paragraph 15 of the Office Action mailed February 9, 2006.

Art Unit: 1773

15. Claims 8, 9, 12 – 16 and 19 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yoshikawa et al. ('892) in view of Hitachi, LTD (JP 62-226413 A), Funayama et al. ('982 A1) and Sato et al. ('851 A1) for the reasons of record as set forth in Paragraph 21 of the Office Action mailed August 8, 2006 and in Paragraph 21 of the Office Action mailed February 9, 2006.

Regarding the amended limitations regarding the bcc crystal structure and the (110) plane, the Examiner notes that Yoshikawa et al. teach that it is known in the art to form soft magnetic films comprising Co and Fe in the form of fine crystals (*Figures and Abstract*) wherein the crystals and (110) plane are preferentially controlled to meet Applicants' claimed limitations inorder to provide a large magnetic flux density and large saturation magnetization (*col. 6, lines 10 – 30; and col. 11, line 35 bridging col. 12, line 59*).

16. Claim 20 is rejected under 35 U.S.C. 103(a) as being unpatentable over Yoshikawa et al. ('892) in view of Hitachi, LTD (JP 62-226413 A), Funayama et al. ('982 A1) and Sato et al. ('851 A1) as applied above, and further in view of Moran (U.S. Patent No. 6,574,854 B1) for the reasons of record as set forth in Paragraph No. 22 of the Office Action mailed August 8, 2006 and in Paragraph 22 of the Office Action mailed February 9, 2006.

Art Unit: 1773

Response to Arguments

17. The rejection of claims 1, 3 – 5, 7, 8, 12 – 16 and 19 - 25 under 35 U.S.C § 112 – 2nd Paragraph

The above noted rejection has been withdrawn in view of applicant(s) arguments, which have been found persuasive.

- 18. The rejection of claims 1, 3 5, 7, 8, 12 16 and 20 25 under 35 U.S.C § 103(a) Various rejections predicated on Hiramoto et al. and Yoshikawa et al.
- 19. The rejection of claims 1, 3 5, 7, 8, 12 16 and 20 25 under 35 U.S.C § 103(a) Various rejections predicated on Funayama et al. and Yoshikawa et al.

Applicant(s) arguments have been considered but are moot in view of the new ground(s) of rejection. In so far as they apply to the present rejection of record, applicant(s) argue that none of the cited references "teaches or suggests columnar crystals having a (110) plane which exhibits the claimed preferred orientation" (pages 7 and 8 of response). The Examiner respectfully disagrees.

Applicant(s) are reminded that "the test for obviousness is not whether features of the secondary reference may be bodily incorporated into the primary reference's structure, nor whether the claimed invention is expressly suggested in any one or all of the references, rather the test is what the combined teachings would have suggested to those of ordinary skill in the art." *Ex parte Martin* 215 USPQ 543, 544 (PO BdPatApp 1981). In the instant case, Yoshikawa et al. is relied upon to teach preferred

Art Unit: 1773

compositions and crystal structures (bcc and (110) plane parallel to the film surface), as noted in the rejection of record above.

Conclusion

- 20. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Fukuzawa et al. (U.S. Patent No. 7,116,527 B1) discloses a hard magnetic film (not soft) comprising a columnar crystal structure substantially identical to applicants' disclosed structure, though the (110) plane is perpendicular to the film surface and not parallel (entire disclosure).
- 21. Any inquiry concerning this communication or earlier communications from the Examiner should be directed to Kevin M. Bernatz whose telephone number is (571) 272-1505. The Examiner can normally be reached on M-F, 8:30 AM - 5:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the Examiner's supervisor, Carol Chaney can be reached on (571) 272-1284. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

KMB February 14, 2007 Kevin M. Bernatz, PhD

Primary Examiner